

Article

Suppressing the Dielectric Loss in Superconducting Qubits through Useful Geometry Design

Haoran He [†], Weilong Wang [†], Fudong Liu , Benzheng Yuan and Zheng Shan ^{*}

State Key Laboratory of Mathematical Engineering and Advanced Computing, Zhengzhou 450001, China; hehaoran0527@126.com (H.H.); wllwang19888@163.com (W.W.); lwfydy@126.com (F.L.); benzhenyuan@outlook.com (B.Y.)

^{*} Correspondence: zzzhengming@163.com

[†] These authors contributed equally to this work.

Abstract: Dielectric loss from different interfacial layers in the superconducting circuit and from external environment may cause superconducting qubit decoherence. Compared to modeling the entire device at once with a numerical solver, quantitatively formulating the dielectric loss can both describe all loss mechanisms and make the optimization more transparent. In this paper, we first analyze the expression formula of dielectric loss, and obtain a design scheme that can reduce the dielectric loss of qubits. That is, we replace the straight junction wires with the tapered junction wires. Based on this scheme, we perform a simulation to optimize the design of junction wires. Finally, a real experiment is conducted to verify our design. The results show that both the T_1 time and T_2 time of qubits are significantly improved.

Keywords: superconducting qubits; dielectric loss; energy participation ratio



Citation: He, H.; Wang, W.; Liu, F.; Yuan, B.; Shan, Z. Suppressing the Dielectric Loss in Superconducting Qubits through Useful Geometry Design. *Entropy* **2022**, *24*, 952. <https://doi.org/10.3390/e24070952>

Academic Editor: Rosario Lo Franco

Received: 2 June 2022

Accepted: 6 July 2022

Published: 8 July 2022

Publisher's Note: MDPI stays neutral with regard to jurisdictional claims in published maps and institutional affiliations.



Copyright: © 2022 by the authors. Licensee MDPI, Basel, Switzerland. This article is an open access article distributed under the terms and conditions of the Creative Commons Attribution (CC BY) license (<https://creativecommons.org/licenses/by/4.0/>).

1. Introduction

Superconducting quantum chips are currently one of the mainstream technologies for realizing quantum computers. Although the scale of qubits has reached a breakthrough to the order of one hundred [1], as the scale increases, the impact of dielectric loss becomes more and more prominent. Over the past decade, many optimization strategies to improve the quality of superconducting qubits have been proposed, including charge and flux noise suppression, detailed design of the electromagnetic environment in which superconducting qubits operate, the search for better materials and fabrication methods, and improved design to minimize equipment losses [2–9]. Dielectric loss, which is one of the earliest processes discovered to cause qubit relaxation, happens when energy is drawn from the qubit's coherent state, making the qubit decay to the ground state from the excited state [10]. It has always been a key factor restricting the coherence time of superconducting qubits [11].

A superconducting qubit can be seen as a resonator composed of a capacitor and a nonlinear inductance in parallel, in which the superconducting Josephson junction provides the nonlinear inductance, and the “0” and “1” states of a qubit are formed by the two lowest energy levels. The structure connecting the Josephson junction to the parallel plate capacitor is called junction wire. The performance of superconducting quantum chips strongly rely on the circuit quality factor Q . For transmon qubits [12], the dielectric loss part of Q can be decomposed into contributions from different materials or regions [13]:

$$Q^{-1} = \sum_i p_i \tan \delta_i, \quad (1)$$

where $\tan \delta_i$ denotes the loss tangent of interface type i , and p_i is the energy participation ratio of interface type i (i = substrate–air (SA), metal–substrate (MS), and metal–air (MA)). To improve the factor Q , one can reduce dielectric losses by optimizing p_i and $\tan \delta_i$. The

strong correlation between dielectric loss and $\tan \delta_i$ will be studied later, and this paper mainly focuses on the influence of energy participation ratio on dielectric loss.

The participation ratio of various materials in the vicinity of the qubit, which represents the proportion of electric field energy contained within the material volume [14], is crucial in determining dielectric loss. It is given by:

$$p_i = \frac{\epsilon_i/2}{W} \int dA t_i |E_i|^2, \quad (2)$$

where t_i is the thickness of the thin dielectric layer, dA is the surface integral instead of the normal volume integral, E_i is the dielectric layer's surface electric field, and ϵ_i is the dielectric layer's dielectric constant.

The total energy of the capacitor is $W \equiv V^2 C/2$, where V denotes the voltage and C denotes the total capacitance. Since the capacitance is easier to determine from the designed distance, it is straightforward to use the length L to characterize the qubit capacitance $C \equiv \epsilon_0 L$ [15].

Three participation ratios can be considered for surface dielectrics [16]:

$$p_{MA} = \frac{1}{\epsilon_{MA}} \frac{t_{MA}}{L\epsilon_0/2} \left[\frac{\epsilon_0}{2} \int_{MA} dA |E_0/V|^2 \right], \quad (3)$$

$$p_{MS} = \frac{\epsilon_s^2}{\epsilon_{MS}} \frac{t_{MS}}{L\epsilon_0/2} \left[\frac{\epsilon_0}{2} \int_{MS} dA |E_0/V|^2 \right], \quad (4)$$

$$p_{SA} = \epsilon_{SA} \frac{t_{SA}}{L\epsilon_0/2} \left[\frac{\epsilon_0}{2} \int_{SA} dA |E_0/V|^2 \right]. \quad (5)$$

ϵ_{MS} is the dielectric constant of the MS interface layer; ϵ_{MA} is the dielectric constant of the MA interface layer; ϵ_{SA} is the dielectric constant of the SA interface layer. The formulas in parentheses represent the surface energy.

It can be clearly seen that generally, due to the large volume and dielectric constant of the substrate, the substrate is the region with the largest energy participation ratio in the qubit, and it is also the key region that determines the scale of the dielectric loss. However, previous studies have shown that the interfacial dielectric loss around the Josephson junction portion of the circuit is the main reason limiting the lifetime of the state-of-the-art transmon qubits. In this paper, the dielectric loss is reduced by optimizing the energy participation ratio p_i through changing the device structure. In particular, the straight junction wires are replaced with the tapered junction wires.

To determine the surface participation ratios of three interfaces: SA, MS, and MA, the finite element method (FEM) technique has traditionally been employed to simulate the transmon qubit design [17,18]. Due to the huge disparity in thickness of these interfacial layers and the scale of the total qubit size or resonator length, precise determination of the surface participation ratios in these domains becomes problematic. Calculating the density of electric field on the interface surface is one answer to this problem. The participation ratio near the three critical interfaces in the plane design can then be computed analytically using conformal mapping based methods [5]. However, the premise of this approach is that the dielectric layer is thicker than the metal layer, which is contrary to the actual situation. The latest method is based on the method proposed in Ref. [6], making use of the corner field scaling and numerical simulation. This approach works with a lossy dielectric with a thickness of a few nanometers and a metal layer roughly 0.1 μm thick, which is similar to the realistic design of a superconducting quantum device.

In this paper, the energy participation ratio formulas of the junction wires are analyzed, and an optimized design that can reduce the dielectric loss is obtained. That is, the straight junction wires are replaced by the tapered junction wires. Then, the qubit structural model

with tapered junction wires is established using HFSS software. By simulation, we obtain the electric field energy of the designed chip. Based on the design parameters of superconducting qubits, we fabricate the chip and conduct a real experiment on the fabricated chip to verify our design. The overall framework of this paper is shown in Figure 1.

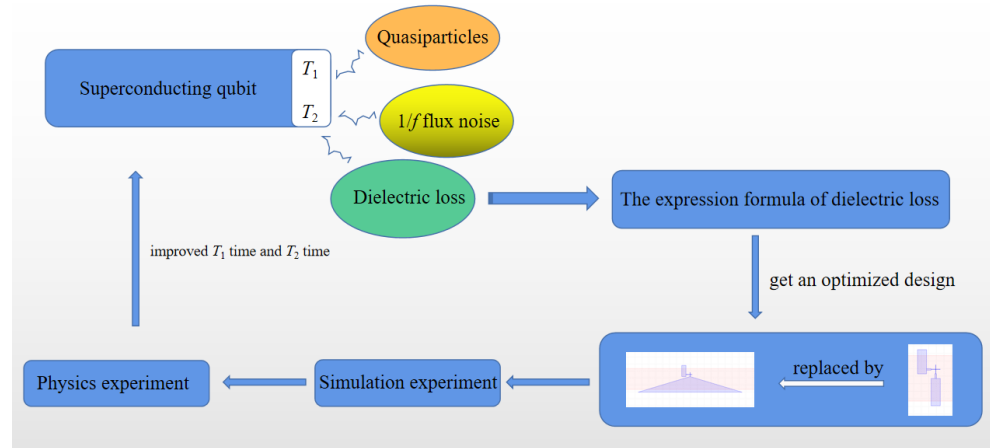


Figure 1. Overall framework. A qubit optimization design is obtained through the analysis of the dielectric loss formula. The design scheme is verified by performing simulation and physical experiments. It is verified that the T_1 time and T_2 time are both improved by our design.

2. Methods and Fabrication

2.1. Comparison of Surface Energy between the Straight and Tapered Junction Wires

The Josephson junction and the capacitor electrodes are connected by two straight junction wires with a total length of $2d$ (Figure 2).

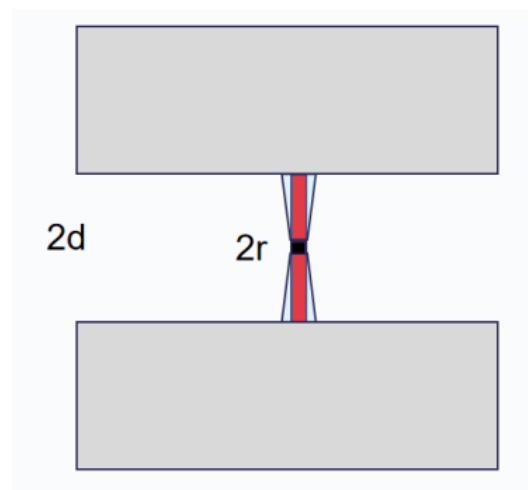


Figure 2. Diagram of the junction wires structure. The black square in the middle is the Josephson junction, the red wires are the straight junction wires, and the tapered junction wires are shown in light blue.

The metal surface energy of the straight wires of a constant width can be derived below [15]:

$$U_{sw}^m \approx \frac{\epsilon V^2 \ln(4r/t) + c_m d}{2 \ln^2(d/r) r'} \tag{6}$$

where c_m is the angular correction for calculating the surface energy of the metal edge.

The surface energy of the substrate for the straight wires with the equal width is [15]:

$$U_{sw}^s \approx \frac{\epsilon V^2}{4} \frac{\ln(4r/t) + c_s}{\ln^2(d/r)} \frac{d}{r}, \tag{7}$$

where c_s is the angular correction for calculating the edge surface energy of the substrate.

This surface energy can be large due to the d/r factor in Equations (6) and (7). Therefore, it could be better to taper the junction wires. Numerical integration of the wires energy gives the metallic surface energy of the tapered junction wires [15]:

$$U_{tw}^m \approx 0.38\epsilon V^2 \frac{\ln(d/r_0)}{S} \frac{\ln(4Sd/r) + c_m}{\ln^2(4/S)}, \tag{8}$$

where S is the slope of the tapered junction wires. Note that, for simplicity but without loss of generality, in this paper only the case of $S = 0.4$ is considered. The substrate surface energy of the tapered junction wires are fitted as [15]:

$$U_{tw}^s \approx 0.15\epsilon V^2 \frac{\ln(d/r_0)}{S} \frac{\ln(4Sd/r) + c_s}{\ln^2(4/S)}. \tag{9}$$

The metallic and substrate surface energy for straight and tapered junctions are plotted in Figure 3. For small distances $d \leq 10 \mu\text{m}$, the results of the two cases are similar. However, for $d > 10 \mu\text{m}$, the tapered loss decreases significantly. Therefore, optimizing the tapered junction wires design becomes increasingly important when using a larger value of d .

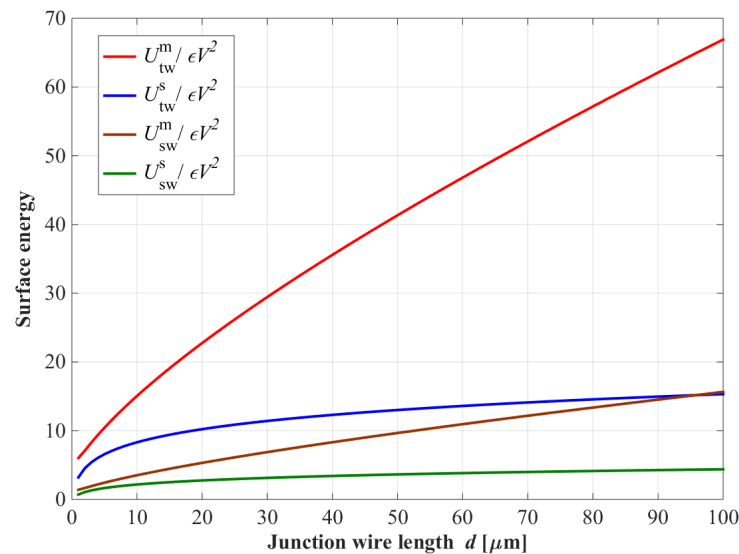


Figure 3. The relationship between the metallic surface energy of straight and tapered junction wires varies and length d . For wire lengths $d \geq 10 \mu\text{m}$, the energy of the tapered junction wire is significantly reduced. The parameters are $t = r_0 = 0.1 \mu\text{m}$ and $S = 0.4$.

2.2. Design and Fabrication

Since $\tan \delta_{SM}$ is sensitive to the choice of materials and the fabrication process of the chip, we have fixed the choice of the substrate material of the chip, the material of the metal film and the fabrication process. In our design, the chip layout is symmetrical up and down as shown in Figure 4. Each part has two different junction wire structures. The spacing between the two qubits is 0.6 mm. The states of qubits Q1 and Q2 are readout via the the resonant cavities, whose frequencies are 6.1 GHz and 6.3 GHz, respectively. The chip fabrication process of the four qubits are the same. A 100 nm aluminum metal film is evaporated on a sapphire substrate by an electron beam evaporation process. We fabricated

Manhattan-style [19,20] Josephson junctions using two aluminium leads, that extend from the pads and overlap each other, separated by an aluminium oxide barrier between them.

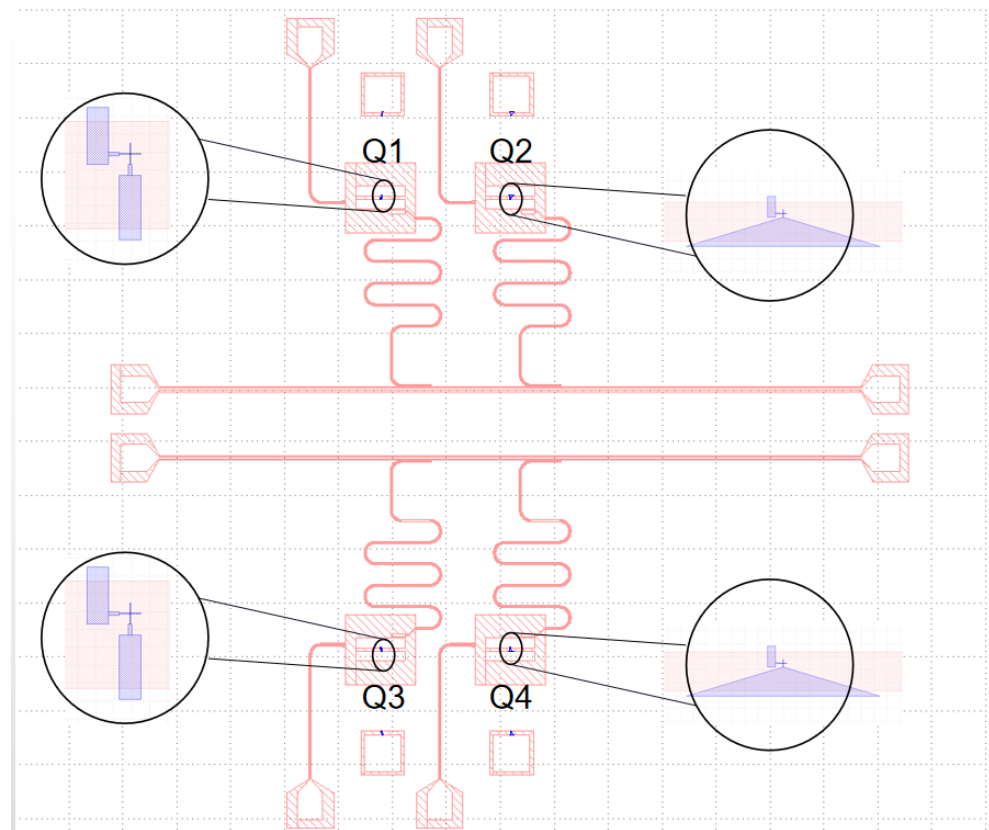


Figure 4. A planar-design 7.5 mm \times 8 mm sample chip. The upper and lower transmission lines of the chip are of symmetrical. The structures of qubits Q1 and Q3 are the same, and both use the straight junction structure. The structures of qubits Q2 and Q4 are the same, and both use the tapered junction structure.

3. Results

3.1. Simulation Experiment

According to Equations (2)–(5), it can be concluded that the dielectric loss is proportional to the interface surface energy U . The value of E can be used to characterize the electric field energy, and thus the loss. Based on the designed superconducting chip structure and fabrication process parameters, the model of the superconducting qubit is established by HFSS. The model is divided into two layers. The upper layer is a two-dimensional qubit structure pattern, including: parallel plate capacitors, junction wires, and the coupling part between the qubit and the readout resonator. The metal material is aluminum and the substrate layer is sapphire with a dielectric constant of 10. Finally, the entire area is covered with a vacuum layer 4 times the thickness of the substrate. The Josephson junction is set as an inductor with a value of 15 nH.

Dielectric loss affects the electric field around the qubit and causes energy relaxation. As shown in Figure 5, compared with the case of the straight junction wires (Figure 5b), the electric field distribution area on the surface of the Josephson junction is significantly reduced, the electric field intensity on the edge surface of the Josephson junction with tapered junction wires (Figure 5c) is significantly reduced as well. This means that by replacing the straight with the tapered wires, the dielectric loss can be reduced, and thus the qubit performance can be improved.

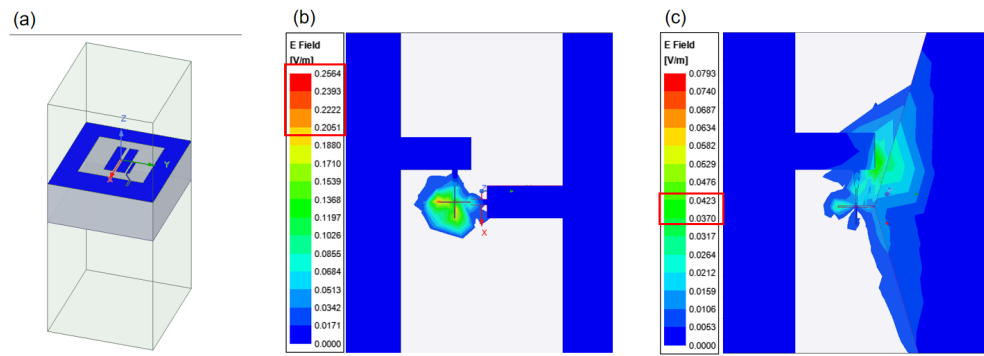


Figure 5. The simulated electric field energy at the substrate surface for two different junction wires. The value in the red box in the figure is the approximate electric field value obtained by the simulation. (a) The model of the superconducting qubit; (b) straight junction wires; and (c) tapered junction wires.

3.2. Physics Experiment

Experimental Setup and Wiring

The chip sample is installed in a dilution refrigerator with a temperature of about 20 mK. The readout wiring scheme is shown in Figure 6. The test results are shown in Table 1.

From the test results shown in Table 1, the T_1 time and the T_2 time of the qubits with tapered junction wires are both higher than those of the qubits with straight junction wires. In specific, the average T_1 time has improved by about 60% and the average T_2 time has improved as high as 600%. Therefore, it is verified by the experiment that the design scheme with tapered junction wires can improve the performance of the superconducting qubits.

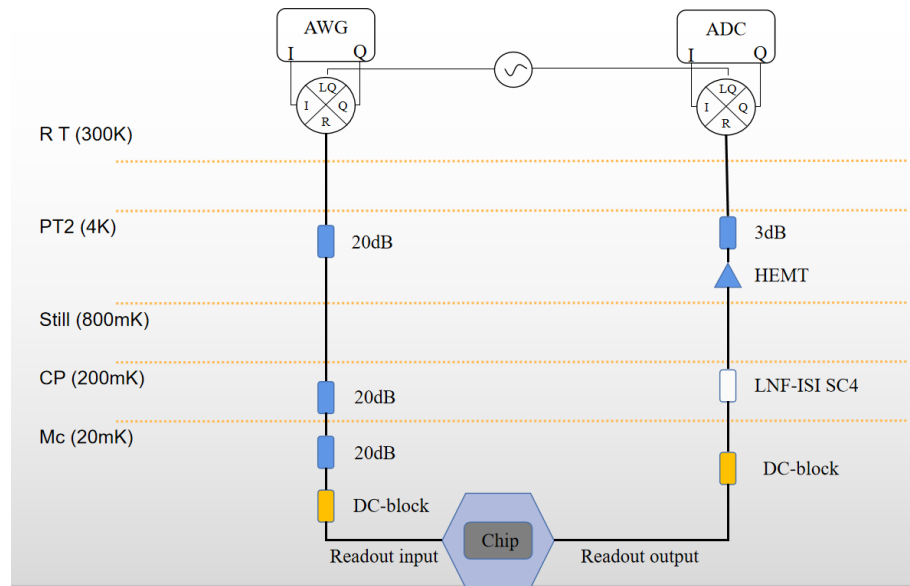


Figure 6. Low temperature test routing and signal synthesis at room temperature.

Table 1. Experimental data. The second column of data represents the shape of the junction wire: *S* is a straight type, and *T* is a tapered type. The third and fourth columns represent the resonator frequency F_r and the qubit frequency F_q , respectively. The idea of measuring T_1 is to give the qubit a π -pulse at the initial moment to excite the qubit to the $|1\rangle$ state, and then measure changes of the qubit state over time. The measurement method of T_2 is the Ramsey measurement. At the initial moment, a $\pi/2$ -pulse with a phase of 0 is given. After waiting for a certain interval time t , another phase is given. In the rotating reference frame, we can obtain a $\pi/2$ -pulse at $|1\rangle$ probability, and finally use the fitting function to get the T_2 time of the system. The last two columns show the measured T_1 time and T_2 time.

Qubit	S/T	F_r (GHz)	F_q (GHz)	T_1 (μ s)	T_2 (μ s)
Q1	S	6.149	5.105	12.7	0.78
Q2	T	6.342	5.287	16.4	3.49
Q3	S	6.159	5.398	6.29	0.77
Q4	T	6.352	5.258	14.1	7.48

4. Conclusions

The formulas that can accurately calculate participation ratios of straight and tapered junction wires is introduced. By studying the formula to quantify the dielectric loss, a graphic design to reduce the dielectric loss is obtained. The traditional finite element method cannot be used to accurately calculate energy participation ratio due to the huge difference between the length and thickness of each structure of the qubit. In this paper, by analyzing the formula of the energy participation ratio, combined with the parameters of superconducting qubit design and process fabrication, the superconducting qubit model is established by HFSS simulation software. The electric field intensity obtained by the simulation indirectly indicates the energy participation ratio. The simulation results show that the energy participation ratio and the dielectric loss can be reduced by replacing the straight junction wires with the tapered junction wires. Finally, our characterization results of two groups of superconducting qubits with different junction wire structures show that the qubits with tapered junction wires have superior performance compared to the ones with straight junction wires. The results of this study provide a useful reference for the geometrical design of superconducting qubits. The next step is to study the influence of the slope *S* of the tapered junction wires on the dielectric loss to further improve the qubit quality.

Author Contributions: Conceptualization, H.H. and W.W.; Data curation, H.H.; Formal analysis, H.H.; Funding acquisition, F.L.; Project administration, F.L. and Z.S.; Supervision, W.W., B.Y. and Z.S.; Writing—original draft, H.H.; Writing—review & editing, W.W., F.L., B.Y. and Z.S. All authors have read and agreed to the published version of the manuscript.

Funding: This research received no external funding.

Data Availability Statement: The data that support the findings of this study are available from the corresponding author upon reasonable request.

Conflicts of Interest: The authors declare no conflict of interest.

References

1. Eagle-Quantum-Processor-Performance. Available online: <https://research.ibm.com/blog/eagle-quantum-processor-performance> (accessed on 27 May 2022).
2. Paik, H.; Schuster, D.I.; Bishop, L.S.; Kirchmair, G.; Catelani, G.; Sears, A.P.; Johnson, B.R.; Reagor, M.J.; Frunzio, L.; Glazman, L.I.; et al. Observation of high coherence in Josephson junction qubits measured in a three-dimensional circuit QED architecture. *Phys. Rev. Lett.* **2011**, *107*, 240501. [CrossRef] [PubMed]
3. Barends, R.; Kelly, J.; Megrant, A.; Sank, D.; Jeffrey, E.; Chen, Y.; Yin, Y.; Chiaro, B.; Mutus, J.; Neill, C.; et al. Coherent Josephson qubit suitable for scalable quantum integrated circuits. *Phys. Rev. Lett.* **2013**, *111*, 080502. [CrossRef] [PubMed]
4. Martinis, J.M.; Megrant, A. UCSB final report for the CSQ program: Review of decoherence and materials physics for superconducting qubits. *arXiv* **2014**, arXiv:1410.5793.

5. Place, A.P.; Rodgers, L.V.; Mundada, P.; Smitham, B.M.; Fitzpatrick, M.; Leng, Z.; Premkumar, A.; Bryon, J.; Vrajitoarea, A.; Sussman, S.; et al. New material platform for superconducting transmon qubits with coherence times exceeding 0.3 milliseconds. *Nat. Commun.* **2021**, *12*, 1779. [[CrossRef](#)] [[PubMed](#)]
6. Wang, C.; Li, X.; Xu, H.; Li, Z.; Wang, J.; Yang, Z.; Mi, Z.; Liang, X.; Su, T.; Yang, C.; et al. Towards practical quantum computers: transmon qubit with a lifetime approaching 0.5 milliseconds. *NPJ Quantum Inf.* **2022**, *8*, 3. [[CrossRef](#)]
7. Gordon, R.T.; Murray, C.E.; Kurter, C.; Sandberg, M.; Hall, S.A.; Balakrishnan, K.; Shelby, R.; Wacaser, B.; Stabile, A.A.; Sleight, J.W.; et al. Environmental radiation impact on lifetimes and quasiparticle tunneling rates of fixed-frequency transmon qubits. *Appl. Phys. Lett.* **2022**, *120*, 074002. [[CrossRef](#)]
8. Gambetta, J.M.; Murray, C.E.; Fung, Y.K.K.; McClure, D.T.; Dial, O.; Shanks, W.; Sleight, J.W.; Steffen, M. Investigating Surface Loss Effects in Superconducting Transmon Qubits. *IEEE Trans. Appl. Supercond.* **2017**, *27*, 1700205. [[CrossRef](#)]
9. Dial, O.; McClure, D.T.; Poletto, S.; Keefe, G.A.; Rothwell, M.B.; Gambetta, J.M.; Abraham, D.W.; Chow, J.M.; Steffen, M. Bulk and surface loss in superconducting transmon qubits. *Supercond. Sci. Technol.* **2016**, *29*, 044001. [[CrossRef](#)]
10. Murray, C.E. Material matters in superconducting qubits. *Mater. Sci. Eng. R Rep.* **2021**, *146*, 100646. [[CrossRef](#)]
11. Woods, W.; Calusine, G.; Melville, A.; Sevi, A.; Golden, E.; Kim, D.K.; Rosenberg, D.; Yoder, J.L.; Oliver, W.D. Oliver Determining Interface Dielectric Losses in Superconducting Coplanar-Waveguide Resonators. *Phys. Rev. Appl.* **2019**, *12*, 014012. [[CrossRef](#)]
12. Koch, J.; Terri, M.Y.; Gambetta, J.; Houck, A.A.; Schuster, D.I.; Majer, J.; Blais, A.; Devoret, M.H.; Girvin, S.M.; Schoelkopf, R.J. Charge-insensitive qubit design derived from the Cooper pair box. *Phys. Rev. A* **2007**, *76*, 538. [[CrossRef](#)]
13. Deng, H.; Song, Z.; Gao, R.; Xia, T.; Bao, F.; Jiang, X.; Ku, H.S.; Li, Z.; Ma, X.; Qin, J.; et al. Titanium Nitride Film on Sapphire Substrate with Low Dielectric Loss for Superconducting Qubits. *arXiv* **2022**, arXiv:2205.03528.
14. Wang, C.; Axline, C.; Gao, Y.Y.; Brecht, T.; Chu, Y.; Frunzio, L.; Devoret, M.H.; Schoelkopf, R.J. Surface participation and dielectric loss in superconducting qubits. *Appl. Phys. Lett.* **2015**, *107*, 162601. [[CrossRef](#)]
15. Martinis, J.M. Optimal design of a superconducting transmon qubit with tapered wiring. *NPJ Quantum* **2022**, *8*, 1–11.
16. Wenner, J.; Barends, R.; Bialczak, R.C.; Chen, Y.; Kelly, J.; Lucero, E.; Mariantoni, M.; Megrant, A.; O'Malley, P.J.J.; Sank, D.; et al. Surface loss simulations of superconducting coplanar waveguide resonators. *Appl. Phys. Lett.* **2011**, *99*, 2012–2015. [[CrossRef](#)]
17. Calusine, G.; Melville, A.; Woods, W.; Das, R.; Stull, C.; Bolkhovskiy, V.; Braje, D.; Hover, D.; Kim, D.K.; Miloshi, X.; et al. Analysis and mitigation of interface losses in trenched superconducting coplanar waveguide resonators. *Appl. Phys. Lett.* **2018**, *112*, 062601. [[CrossRef](#)]
18. Sandberg, M.; Vissers, M.R.; Kline, J.S.; Weides, M.; Gao, J.; Wisbey, D.S.; Pappas, D.P. Etch induced microwave losses in titanium nitride superconducting resonators. *Appl. Phys. Lett.* **2012**, *100*, 262605. [[CrossRef](#)]
19. Potts, A.; Parker, G.J.; Baumberg, J.J.; De Groot, P.A.J. CMOS compatible fabrication methods for submicron Josephson junction qubits. *IEE Proc.-Sci. Meas. Technol.* **2001**, *107*, 225–228. [[CrossRef](#)]
20. Costache, M.V.; Bridoux, G.; Neumann, I.; Valenzuela, S.O. Lateral metallic devices made by a multiangle shadow evaporation technique. *J. Vac. Sci.* **2015**, *30*, 04E105. [[CrossRef](#)]